

## ELEDE® 380E & 380F ICP Etch System

### System Overview

ELEDE 380E & 380F are ICP etchers with high throughput and excellent performance for the production of patterned sapphire substrates (PSS) and nanopatterned sapphire substrates (NPSS) in III-V LED processing.

<b>Substrate Size:</b>	50 mm, 100 mm, 150 mm
<b>Application compounds:</b>	Sapphire (Al <sub>2</sub> O <sub>3</sub> )
<b>Technology Markets:</b>	III-V LED
<b>Process Modules:</b>	380E—1 module 380F—2 modules



ELEDE 380E PSS Etcher

### Processes

- Patterned Sapphire Substrates
- Nanopatterned Sapphire Substrates

### Production Advantages

- Simultaneous high etch rate & selectivity
- Temperature-controlled chamber/exhaust surfaces extend preventive maintenance interval
- Chamber design ensures excellent gas flow uniformity
- Process-tunable profile control
- Stable particle performance over entire maintenance period
- Two tray auto transfer system maximizes productivity and minimizes particle contamination
- Optimized process kit design, longer consumable life and low consumable parts cost
- Active Wafer Centering function ensures exact tray placement



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